

PATENT APPLICATION
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

SUZUKI, Takako, et al.

Attorney Docket No.: Q67844

Divisional of Appln. No.: 09/322,978

Group Art Unit: 1752

Confirmation No.: Unknown

Examiner: Unknown

Filed: February 28, 2002

For: POSITIVE PHOTORESIST COMPOSITION AND PROCESS FOR FORMING
RESIST PATTERN USING SAME

PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Sir:

Prior to examination, please amend the above-identified application as
follows:

IN THE SPECIFICATION:

Amend the specification by inserting before the first line the
sentence:

This is a divisional of Application No. 09/322,978 filed June 1, 1999, allowed;
the disclosure of which is incorporated herein by reference.

Please amend the specification as follows:

Replace the 2nd paragraph of Page 1 with the following paragraph:

10034204-022302

2/A
D.G.
4-24-02

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